

Title (en)

THERMALLY CURED UNDERLAYER FOR LITHOGRAPHIC APPLICATION

Title (de)

THERMISCH GEHÄRTETE UNTERSCHICHT FÜR DIE LITHOGRAPHIE

Title (fr)

SOUS-COUCHE DURCIE THERMIQUEMENT POUR APPLICATION LITHOGRAPHIQUE

Publication

**EP 1373331 A2 20040102 (EN)**

Application

**EP 02733834 A 20020307**

Priority

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- US 27552801 P 20010313

Abstract (en)

[origin: WO02073307A2] Thermally cured undercoat for use in lithography of a thermally cured composition comprising a hydroxyl-containing polymer, an amino cross-linking agent and a thermal acid generator, wherein the hydroxyl containing polymer is a polymer comprising units m, n and o of the formula (I) wherein R<1> is H or methyl; R<2> is a substituted or unsubstituted C6-C14 aryl acrylate or C6-C14 aryl methacrylate group wherein the substituted groups may be phenyl, Cl-4 alkyl or C1-4 alkoxy; R<3> is a hydroxyl functionalized Cl-C8 alkyl acrylate, methacrylate or C6-C14 aryl group, R<4> is a C1-C10 linear or branched alkylene; p is an integer of from 1 to 5 with the proviso that there are no more than thirty carbon atoms in the [-R<4>O]<sub>p</sub>; R<5> is a Cl-C10 linear, branched or cyclic alkyl, substituted or unsubstituted C6-C14 aryl, or substituted or unsubstituted C7-C15 alicyclic hydrocarbon; and m is about 40 to 70, n is about 15 to 35 and o is about 15 to 25.

IPC 1-7

**C08F 8/32; C08F 36/20; C08F 236/20; C08L 45/00; B32B 27/06; G03C 1/93**

IPC 8 full level

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